WHAT IS CLAIMED IS:

- 1. A low-reflectance conductive film characterized in that said low-reflectance conductive film comprises at least two films which are a conductive film comprising conductive fine particles and a low-refraction film formed on said conductive film, having a lower refractive index than said conductive film, and that said conductive film comprises a resistance-lowering material.
- The low-reflectance conductive film according to
 Claim 1, wherein said conductive fine particles are fine particles of tin-doped indium oxide or fine particles of antimony-doped tin oxide.
 - 3. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound and/or titanium oxide.
 - 4. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound, and said sulfur compound is at least one kind selected from the group consisting of α -lipoic acid, α -lipoamide, thiodipropionic acid, sodium thiosulfate, thiourea, and sodium thioglycollate.

20

5. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is a sulfur compound, and the content of said sulfur compound in said conductive film, when converted to the mass of sulfur in said conductive film, is from 0.1 to 10 mass% to the conductive fine particles in the conductive film.

- 6. The low-reflectance conductive film according to Claim 1, wherein said resistance-lowering material is titanium oxide, and the content of said titanium oxide in the conductive film is from 0.1 to 20 mass% to the
- 7. The low-reflectance conductive film according to Claim 1, wherein said conductive film has a film thickness of from 5 to 200 nm, and said low-refraction film has a film thickness of from 5 to 150 nm.

conductive fine particles in the conductive film.

- 10 8. A colored low-reflectance conductive film according to Claim 1, wherein a colored film containing therein a coloring component is formed on a side opposite to the low refraction film of said conductive film.
- 9. The colored low-reflectance conductive film according to Claim 8, wherein said coloring component is carbon black or titanium black.
 - 10. The colored low-reflectance conductive film according to Claim 8, wherein said colored film has a film thickness of from 5 to 200 nm.
- 20 11. A coated article comprising a substrate on which there is formed said low-reflectance conductive film as defined in Claim 1.

thereof.

12. A display apparatus wherein said coated article as defined in Claim 11 is incorporated so as to position said low-reflectance conductive film or said colored low-reflectance conductive film at an external surface

- 13. An X-coating liquid comprising a solvent, conductive fine particles, and a resistance-lowering material.
- 14. A conductive film forming coating liquid as defined in Claim 13, wherein the concentration of said conductive fine particles is from 0.01 to 20 mass% to the total mass of said coating liquid, said resistance-lowering material is a titanium oxide source, and the content of said titanium oxide source, when converted to the mass of titanium oxide, is from 0.1 to 20 mass% to the conductive fine particles.
 - 15. A low-refraction film forming coating liquid comprising a solvent, a silicon compound, and a resistance-lowering material.
- 16. The low-refraction film forming coating liquid according to Claim 15, wherein said silicon compound is a 15 silicon alkoxide, with the content of said silicon alkoxide being in an amount of from 0.1 to 30 mass% in terms of the solid component concentration of SiO2 to the total amount of said low-refraction film forming coating liquid, and said resistance-lowering material is a sulfur compound, with the content of said sulfur compound being in an amount of from 0.01 to 1.5 mass% to the total amount of said low-refraction film forming coating liquid. 17. The low-refraction film forming coating liquid according to Claim 15, wherein said silicon compound is a 25 silicon alkoxide, with the content of said silicon alkoxide being in an amount of from 0.1 to 30 mass% in

terms of the solid component concentration of SiO₂ to the total amount of said low-refraction film forming coating liquid, and said resistance-lowering material is a titanium oxide source, with the content of said titanium oxide source, when converted into the amount of titanium oxide, being in an amount of from 0.01 to 1.0 mass% to the total amount of said low-refraction film forming coating liquid.

- 18. A low-reflectance conductive film manufacturing

 method for forming a low-reflectance film by coating onto
 a substrate a conductive film forming coating liquid
 which contains conductive fine particles, and then
 coating a low-refraction film forming coating liquid
 which contains a resistance-lowering material.
- 19. A colored low-reflectance film manufacturing method according to Claim 18 for forming a colored low-reflectance film by coating onto a substrate a colored film forming coating liquid which contains a coloring component, prior to the coating of said conductive film forming coating liquid.
 - 20. A low-reflectance conductive film manufacturing method characterized by coating onto a substrate a conductive film forming coating liquid which contains conductive fine particles, then coating a low-refraction film coating liquid, thereby forming a low-reflectance conductive film, and irradiating said low-reflectance conductive film with a light having energy greater than

the band gap of said conductive particles, thereby reducing the surface resistance value of said lowreflectance film in comparison with the case where the irradiation of said light is not carried out.

21. A low-reflectance conductive film manufacturing method for forming a low-reflectance conductive film by coating onto a substrate a conductive film forming coating liquid which contains conductive fine particles, then coating a low-refraction film forming coating liquid, thereby forming the low-refraction film, characterized in that said conductive film forming coating liquid and/or said low-refraction film forming coating liquid contains a titanium oxide source, and the surface resistance value of said low-reflectance film is reduced by irradiating 15 said low-reflectance conductive film with light having energy greater than the band gap of titanium oxide, in comparison with the case where the irradiation of said light is not carried out.

10